

	Hits	Search Text	DBs	Time Stamp
10	10	(photoresist and substrate and (foot feet)).clm.	US - PGPUB	2005/12/09 15:50
11	51	(photoresist and substrate and basic).clm.	US - PGPUB	2005/12/09 15:51
12	3	(photoresist and substrate and basic with (treating treated treat)).clm.	US - PGPUB	2005/12/09 15:51

	Hits	Search Text	DBs	Time Stamp
1	4	photoresist with (foot feet) and substrate and basic with (treat treating treated)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:44
2	104	photoresist same substrate and (treat treating treated) with basic	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:36
3	70	photoresist same substrate and (treat treating treated) near5 basic	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:36
4	91	photoresist and substrate and (treat treating treated) near5 basic	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:36
5	20	photoresist same substrate and (treat treating treated) near5 basic same photoresist	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:39
6	39	photoresist same substrate and (treat treating treated) near5 basic same substrate	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:40
7	30	photoresist same substrate and (treat treating treated) near5 basic same substrate and photoresist with (pattern patterning patterned develop developing developed)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:40
8	8	photoresist same (foot feet) and substrate and basic with (treat treating treated)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/09 15:44
9	1	(photoresist and substrate and (foot feet) and basic).clm.	US -PGPUB	2005/12/09 15:51